

WetSec201

Wet Process Monitoring For Semiconductor, FPD and Solar cell manufacturing

CI-SEMI's in-line, wet process analysis system, the WetSpec201, enables non-contact real-time monitoring and closed-loop control of chemical composition in wet process applications. The WetSpec201 is the single-channel version of the well known eight channel monitor, the WetSpec200 and provides a cost-effective, fast and small footprint solution. A perfect solution for the OEM and end user.

The WetSpec201 is ideal for monitoring of cleaning, stripping and etching and texturing chemistries. Based on CI-SEMI's proprietary hardware and novel algorithms, the WetSpec201 measures the properties of the solution by measuring the absorption spectrum in the near infrared (NIR) quickly and accurately without labor and material waste. The system's versatile software models enable soft-switch between different chemistries. When integrated into a control and spiking system, the WetSpec201 enables tighter process control and identifies process excursions before they affect yield.

Features & Benefits

- In-line, real-time monitoring of chemical concentration of liquids
- Cost efficient and small footprint
- No need for chemical sampling or dilution
- Short measurement time and low operational costs
- Simple switching between different chemistries
- Analysis of complex (multi-component) chemistries
- Real-time measurement enables closed loop control



WetSec201

Schematic System Configuration



Typical Applications *

| Application | Component | Range wt% |
|--------------------|-----------|-----------|
| SC1 | NH4OH | 0-1.5 |
| | H2O2 | 0-3 |
| SC2 | HCl | 0-4 |
| | H2O2 | 0-8 |
| DSP | H2SO4 | 8-13 |
| HF/HCl | H2O2 | 2-5 |
| | HF | 0-20 |
| HF | HCl | 0-1.2 |
| | HF | 0-20 |
| Hydrofluoric | HF | 22-27 |
| Peroxide | H2O2 | 13-17 |
| Buffered Oxide | HF | 1-5 |
| Etch | NH4F | 16-24 |
| Nitric/Acetic Acid | HNO3 | 1-4 |
| ACT 970 | CH3COOH | 8-12 |
| EKC265 | H2O | 14-19 |
| ST-250 | H2O | 16-28 |
| Peroxide in CMP | H2O2 | 34-38 |
| Slurry | H2O2 | 0-5 |
| Ammonium Hydroxide | NH4OH | 0-5 |
| KOH | KOH | 0-50 |
| HF/HNO3 | HF | 10-20 |
| | HNO3 | 25-35 |
| Al. Etch | HNO3 | 3-6 |
| | CH3COOH | 3-6 |
| | H3PO4 | 65-75 |

* Other chemistries/ranges supported per request

Key Specifications

| | |
|--------------------------|--|
| Measurement method | Fiber-optic remote NIR spectroscopy |
| Calibration method | Chemometrics |
| Multi-channel ability | Up to eight measurement channels |
| Time per measurement | Up to 30 sec (Application depended) |
| Sample conditioning | None required |
| Temperature compensation | Automatic and continuous |
| Wetted materials | Process compatible cell body (Teflon/PEEK/SS), sapphire windows, approved seal materials |
| Communication | RS232 / Analog / Ethernet |
| Fiber length | Up to 200m |
| Size | Single 2U 19" rack unit |